

## Electronic Supplementary Information

# Robust and Transparent Membrane of Crystalline Silicone via Melt-Drawing Technique

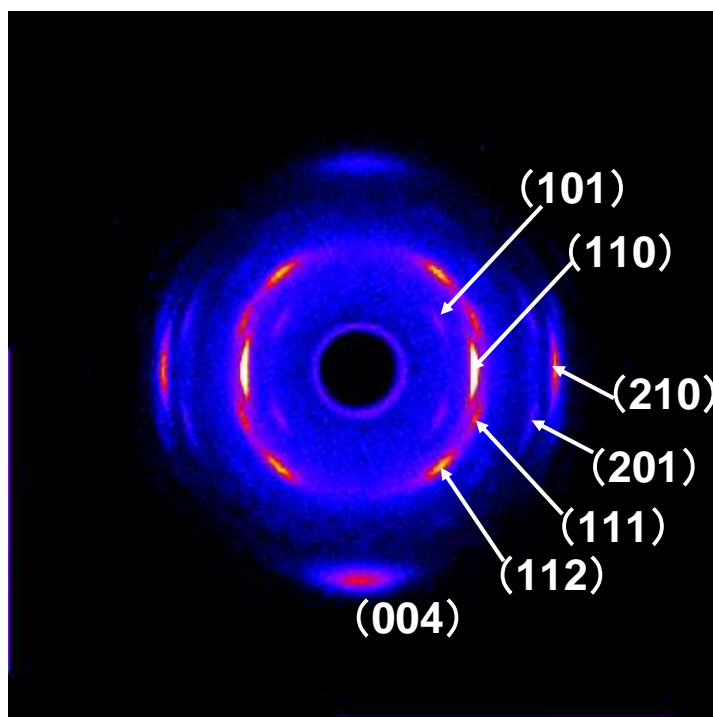
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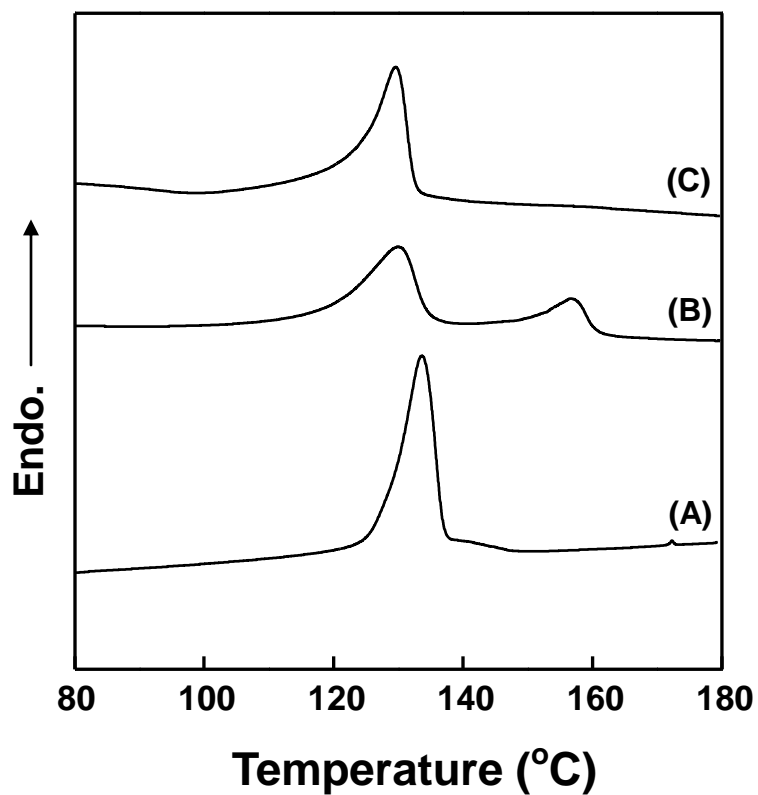
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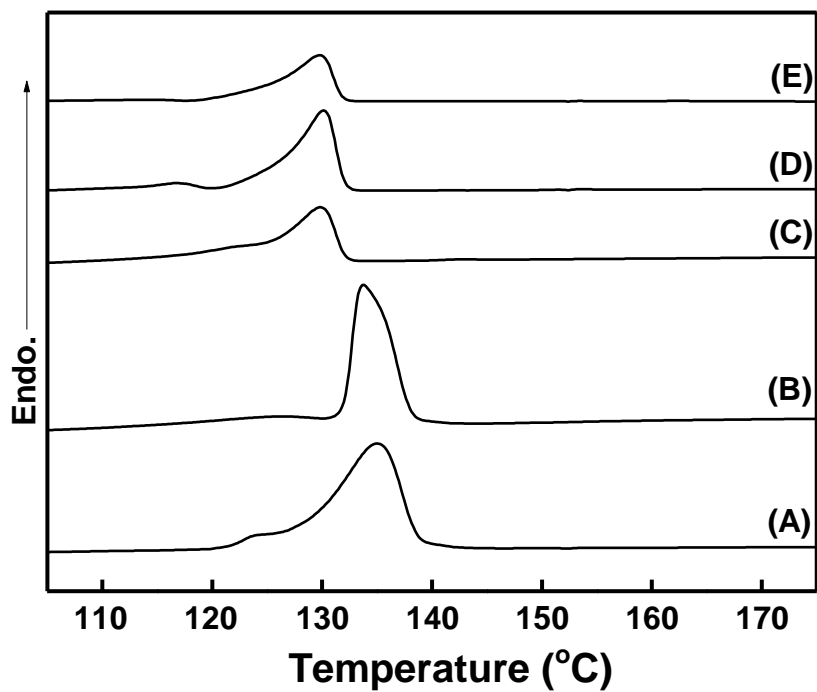


**Fig S1.** An enlarged WAXD pattern for the membrane roll-drawn at 140°C with the reflection indexes.

Roll-drawing direction is vertical.



**Fig S2** DSC curves for the membranes roll-drawn at 120°C (A), 140°C (B) and 160°C (C). The heating rate was 2°C/min.



**Fig S3** DSC curves for the un-drawn SGC film annealed at 120°C (A), 130°C (B), 140°C (C), 150°C (D) and 160°C (E). Heating rate was 10°C/min.